

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	4727	(x-ray OR xray OR ultraviolet OR EUV) SAME (lithograph\$2 OR photolithograph\$2)	USPAT	2000/06/14 08:26
2	BRS	L2	569	secondary ADJ light ADJ source	USPAT	2000/06/14 08:29
3	BRS	L3	17	1 AND 2	USPAT	2000/06/14 09:03
4	BRS	L4	21956	raster	USPAT	2000/06/14 08:30
5	BRS	L5	0	3 AND 4	USPAT	2000/06/14 08:30
6	BRS	L6	14322	honeycomb	USPAT	2000/06/14 08:31
7	BRS	L7	96	4 AND 6	USPAT	2000/06/14 08:31
8	BRS	L8	0	3 AND 6	USPAT	2000/06/14 08:32
9	BRS	L9	10500	(x-ray OR xray) SAME (exposure OR illumination)	USPAT	2000/06/14 09:04
10	BRS	L10	26	2 AND 9	USPAT	2000/06/14 09:05
11	BRS	L11	0	4 AND 10	USPAT	2000/06/14 09:05
12	BRS	L12	0	6 AND 10	USPAT	2000/06/14 09:05
13	BRS	L13	1338	(193 ADJ nm) OR 193nm	USPAT	2000/06/14 09:28
14	BRS	L14	6	3 AND 13	USPAT	2000/06/14 09:30
15	BRS	L15	5	10 AND 13	USPAT	2000/06/14 09:30

	Document ID	Title	Current OR	Inventor
1	US 6031238 A	Projection aligner for integrated circuit fabrication	250/492.2	Fujinoki, Akira , et al.
2	US 5825043 A	Focusing and tilting adjustment system for lithography aligner, manufacturing apparatus or inspection apparatus	250/548	Suwa, Kyoichi
3	US 5805626 A	Single-crystal lithium tetraborate and method making the same, optical converting method and converter device using the single-crystal lithium tetraborate, and optical apparatus using the optical converter device	372/41	Komatsu, Ryuichi , et al.
4	US 5669708 A	Optical element, production method of optical element, optical system, and optical apparatus	362/341	Mashima, Kiyoto , et al.
5	US 5581605 A	Optical element, production method of optical element, optical system, and optical apparatus	378/84	Murakami, Katsuhiko , et al.
6	US 5471278 A	Cadmium/rare gas discharge lamp of the short arc type, as well as projection exposure device using the same	355/67	Yasuda, Yukio , et al.

	Document ID	Title	Current OR	Inventor
1	US 5872618 A	Projection exposure apparatus	355/53	Nagayama, Tadashi , et al.
2	US 5825043 A	Focusing and tilting adjustment system for lithography aligner, manufacturing apparatus or inspection apparatus	250/548	Suwa, Kyoichi
3	US 5715039 A	Projection exposure apparatus and method which uses multiple diffraction gratings in order to produce a solid state device with fine patterns	355/53	Fukuda, Hiroshi , et al.
4	US 5669708 A	Optical element, production method of optical element, optical system, and optical apparatus	362/341	Mashima, Kiyoto , et al.
5	US 5581605 A	Optical element, production method of optical element, optical system, and optical apparatus	378/84	Murakami, Katsuhiko , et al.

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1	US 6031238 A	Projection aligner for integrated circuit fabrication	250/492.2	Fujinoki, Akira , et al.
2	US 6016187 A	Exposure apparatus and method	355/53	Noguchi, Minoru , et al.
3	US 5955243 A	Illumination optical system and method of manufacturing semiconductor devices	430/311	Tanitsu, Osamu
4	US 5825844 A	Optical arrangement and illumination method	378/34	Miyake, Akira , et al.
5	US 5825043 A	Focusing and tilting adjustment system for lithography aligner, manufacturing apparatus or inspection apparatus	250/548	Suwa, Kyoichi
6	US 5805626 A	Single-crystal lithium tetraborate and method making the same, optical converting method and converter device using the single-crystal lithium tetraborate, and optical apparatus using the optical converter device	372/41	Komatsu, Ryuichi , et al.
7	US 5767949 A	Exposure apparatus and method	355/67	Noguchi, Minoru , et al.

	Document ID	Title	Current OR	Inventor
8	US 5669708 A	Optical element, production method of optical element, optical system, and optical apparatus	362/341	Mashima, Kiyoto, et al.
9	US 5638211 A	Method and apparatus for increasing the resolution power of projection lithography exposure system	359/559	Shiraishi, Naomasa
10	US 5581605 A	Optical element, production method of optical element, optical system, and optical apparatus	378/84	Murakami, Katsuhiko, et al.
11	US 5534970 A	Scanning exposure apparatus	355/53	Nakashima, Toshiharu, et al.
12	US 5526094 A	Exposure apparatus and method	355/53	Noguchi, Minoru, et al.
13	US 5471278 A	Cadmium/rare gas discharge lamp of the short arc type, as well as projection exposure device using the same	355/67	Yasuda, Yukio, et al.
14	US 5333050 A	Measuring method and apparatus for measuring the positional relationship of first and second gratings	356/356	Nose, Noriyuki, et al.
15	US 5329333 A	Exposure apparatus and method	355/53	Noguchi, Minoru, et al.

	Document ID	Title	Current OR	Inventor
16	US 5010230 A	Laser processor	219/121.62	Uemura, Tsunesaburo
17	US 4905041 A	Exposure apparatus	355/53	Aketagawa, Masato

	Document ID	Title	Current OR	Inventor
1	US 6069937 A	Illumination apparatus	378/119	Oshino, Tetsuya , et al.
2	US 6040909 A	Surface position detecting system and device manufacturing method using the same	356/375	Hasegawa, Masanobu , et al.
3	US 6038279 A	X-ray generating device, and exposure apparatus and semiconductor device production method using the X-ray generating device	378/34	Miyake, Akira , et al.
4	US 6016187 A	Exposure apparatus and method	355/53	Noguchi, Minoru , et al.
5	US 5896438 A	X-ray optical apparatus and device fabrication method	378/34	Miyake, Akira , et al.
6	US 5872618 A	Projection exposure apparatus	355/53	Nagayama, Tadashi , et al.
7	US 5825844 A	Optical arrangement and illumination method	378/34	Miyake, Akira , et al.
8	US 5825043 A	Focusing and tilting adjustment system for lithography aligner, manufacturing apparatus or inspection apparatus	250/548	Suwa, Kyoichi
9	US 5767949 A	Exposure apparatus and method	355/67	Noguchi, Minoru , et al.
10	US 5715039 A	Projection exposure apparatus and method which uses multiple diffraction gratings in order to produce a solid state device with fine patterns	355/53	Fukuda, Hiroshi , et al.

	Document ID	Title	Current OR	Inventor
11	US 5677939 A	Illuminating apparatus	378/34	Oshino, Tetsuya
12	US 5669708 A	Optical element, production method of optical element, optical system, and optical apparatus	362/341	Mashima, Kiyoto, et al.
13	US 5640284 A	Optical reflector, illumination optical system, light source system and illumination optical apparatus	359/869	Tanitsu, Osamu, et al.
14	US 5631721 A	Hybrid illumination system for use in photolithography	355/71	Stanton, Stuart, et al.
15	US 5581605 A	Optical element, production method of optical element, optical system, and optical apparatus	378/84	Murakami, Katsuhiko, et al.
16	US 5526094 A	Exposure apparatus and method	355/53	Noguchi, Minoru, et al.
17	US 5524039 A	Projection exposure apparatus	378/34	Kamon, Kazuya
18	US 5422205 A	Micropattern forming method	430/5	Inoue, Soichi, et al.
19	US 5399877 A	Radiation sensitive area detection device and method	250/581	Carter, Daniel C., et al.

	Document ID	Title	Current OR	Inventor
20	US 5333050 A	Measuring method and apparatus for measuring the positional relationship of first and second gratings	356/356	Nose, Noriyuki, et al.
21	US 5329333 A	Exposure apparatus and method	355/53	Noguchi, Minoru, et al.
22	US 5302999 A	Illumination method, illumination apparatus and projection exposure apparatus	355/1	Oshida, Yoshitada, et al.
23	US 5121160 A	Exposure method and apparatus	355/53	Sano, Naoto, et al.
24	US 4814829 A	Projection exposure apparatus	355/43	Kosugi, Masao, et al.
25	US 4765701 A	Illuminator optical fiber rod	362/560	Cheslak, Leonard W.
26	US 4281645 A	Method and apparatus for monitoring metabolism in body organs	600/324	Jobsis, Frans F.